

Search Notes

Application No.

10/612,836

Examiner

Stephen W. Smoot

Applicant(s)

WEIMER ET AL.

Art Unit

2813

SEARCHED

Class	Subclass	Date	Examiner
438	301	9/16/2004	SWS
438	303	9/16/2004	SWS
438	595	9/16/2004	SWS
438	786	9/16/2004	SWS
438	791	9/16/2004	SWS
427	255.29	9/16/2004	SWS
427	255.39	9/16/2004	SWS
427	255.393	9/16/2004	SWS
427	255.394	9/16/2004	SWS
Updated	Above	12/16/2004	SWS

*S.W.S.**S.W.S.***INTERFERENCE SEARCHED**

Class	Subclass	Date	Examiner
Same as Above		12/16/2004	<i>S.W.S.</i> SWS

**SEARCH NOTES
(INCLUDING SEARCH STRATEGY)**

	DATE	EXMR
Key Words: Chemical Vapor Deposition - CVD, Tetrachlorosilane - TCS, Hexachlorodisilane - HCD;	9/16/2004	<i>S.W.S.</i> SWS
Deuterated Silicon Nitride - Spacer; Deuterated Silicon Oxynitride;	9/16/2004	<i>S.W.S.</i> SWS
Anisotropic Etching - Gate Stack; Ion Implantation - Source/Drain Regions; DRAM.	9/17/2004	<i>S.W.S.</i> SWS
Updated Above Search	12/16/2004	<i>S.W.S.</i> SWS
Search Tools - EAST (attached): USPAT; US PG PUBS; Derwent; EPO; JPO; IBM TDB	9/16/2004 <i>12-16-04</i>	SWS <i>S.W.S.</i>